

Form PTO-1449

**INFORMATION DISCLOSURE CITATION
IN AN APPLICATION**

(Use several sheets if necessary)

Docket Number
12-1233

Application Number
Herewith

Applicant
Lammert

Filing Date
Herewith

Group Art Unit
N/A

10/30/01
10/01/6693
U.S. PTO

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER							DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROP.
RLD	5	3	5	2	9	1	1	10/04/1994	Grossman	257	198	10/28/1991
RLD	5	4	8	6	4	8	3	01/23/1996	Lammert	435	666	09/27/1994
RLD	5	8	0	4	4	8	7	09/08/1998	Lammert	438	319	07/10/1998
RLD	5	9	9	4	1	9	4	11/30/1999	Lammert	438	319	05/07/1998

FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	Translation	
					Yes	No

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

RLD	Schuppert, et al., "Anisotropic Plasma Etching of Polymers Using a Cryo-Cooled Resist Mask, <i>J. Vac. Sci. Technol. A</i> 18(2), March/April 2000, pages 385-387
RLD	Zhao, et al., "Reactive Ion Etching of Silicon Containing Polynorborenes", School of Chemical Engineering, Georgia Institute of Technology, pages 1-30.

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.